	Application No.	Applicant(s)
Notice of Allowability	10/690,399	WILLIFORD, ETHAN
	Examiner	Art Unit
	Wai-Sing Louie	2814
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.		
1. This communication is responsive to 3/22/06.		
2. The allowed claim(s) is/are <u>1-9</u> .		
3.		
Attachment(s) 1. ☑ Notice of References Cited (PTO-892) 2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948) 3. ☐ Information Disclosure Statements (PTO-1449 or PTO/SB/O Paper No./Mail Date 4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview Summary Paper No./Mail Da 98), 7. ☐ Examiner's Amend	te

DETAILED ACTION

The argument in the response to the non-final rejection is persuasive and the non-final rejection of previous office action is withdrawn. Claims 1-9 are allowed.

Allowable Subject Matter

The following is an examiner's statement of reasons for allowance:

The prior art of record does not disclose or suggest either in singularly or in combination the following limitations and other elements in the claims. Reference Lilja et al. (US 5,286,981) do not disclose:

- A gate having at least one implant aperture formed there (Lilja et al. disclose a split gate).
- Lightly doped extensions (LDDs) under the gate, where the LDDs and the channel internal implanted region being substantially equivalently doped.

Reference Choi et al. (US 6,936,517) do not disclose:

- A gate having at least one implant aperture formed there (Choi et al. disclose an aperture in the intermediate product, but the aperture is plugged with a gate electrode 50).
- Lightly doped extensions (LDDs) under the gate, where the LDDs and the channel internal implanted region being substantially equivalently doped.

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Therefore, the above references do not disclose the claimed invention of present application and claims 1-9 are allowed.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Wai-Sing Louie whose telephone number is (571) 272-1709. The examiner can normally be reached on 7:30 AM to 4:00 PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael Fahmy can be reached on (571) 272-1705. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

Wsl June 7, 2006.

//LOXIG PHAM PRIMARY EXAMINER